

# Laboratory Report

Microwave Plasma Chemical Wave Deposition

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## Objectives:

1. To study the Microwave Plasma Chemical Vapor Deposition (MPCVD) for plasma processing of carbon materials and the growth of high-quality single crystal diamond (SCD).
2. To study the Optical emission spectroscopy (OES) of hydrogen ( $H_2$ ) plasma and identify the Balmer  $H_\alpha$  and  $H_\beta$  lines.
3. To study the OES of hydrogen and methane ( $CH_4$ ) plasma and identify the  $H_\alpha$ ,  $H_\beta$ ,  $H_2$  - Fulcher band,  $C_2$  (swan bands,  $\Delta\nu = -1, 0, 1$ ), and CH band.
4. To estimate the electron temperature ( $T_e$ ) using the  $H_\alpha$  and  $H_\beta$  line intensities in  $H_2$  -  $CH_4$  plasma.

## Theory:

### 1. MPCVD

MPCVD is a versatile and widely used technique for synthesizing high-quality diamond films and other carbon-based materials. This method uses the microwave energy to create a plasma environment, enabling the growth of diamond crystals with exceptional purity and quality. In MPCVD, a gas mixture typically composed of  $H_2$  and a carbon source, such as  $CH_4$ , is introduced into a vacuum chamber. Microwaves are then used to ionize the gases, creating a plasma that contains high-energy ions, radicals, and electrons. These reactive species interact with a substrate leading to the deposition of diamond films.

### 2. Magnetron

A magnetron is a high-powered vacuum tube that generates microwaves using the interaction of a stream of electrons with a magnetic field. It consists of a cylindrical cathode placed at the center of an anode block, which typically has resonant cavities. When a high voltage is applied between the cathode and anode, electrons are emitted from the cathode and accelerated towards the anode. A strong magnetic field, perpendicular to the electric field, is applied, causing the electrons to spiral and create a circular motion around the cathode. As these electrons pass by the resonant cavities in the anode block, they induce high-frequency oscillations, generating microwaves.

### 3. Vacuum system

The vacuum system is an integral part of the MPCVD technique, ensuring the creation of a controlled environment necessary for the deposition process. It allows precise control over gas phase composition, pressure, and temperature, which are essential for the growth of defect-free and high-purity materials. The rotary pump, also known as a roughing pump, is used to create a primary vacuum in the deposition chamber by reducing the pressure from atmospheric level to a medium vacuum range.

### 4. Pyrometer

Digital pyrometers work on the principle of detecting infrared radiation emitted by an object. By measuring this radiation, the pyrometer can determine the temperature of the object without physically touching it. The lens used in the pyrometer collects the infrared radiation emitted by the object and focuses it onto the detector. The detector converts the focused infrared radiation into an electrical signal. The signal processor amplifies and processes the electrical signal to calculate the temperature.

### 5. Optical emission spectroscopy

OES is based on the principle that atoms and ions emit light at characteristic wavelengths when they return to a lower energy state after being excited. The energy source, such as a plasma, provides sufficient energy to excite the atoms or ions in the sample. As these excited species return to their ground state, they emit light at specific wavelengths that correspond to the energy differences between the excited and ground states. The spectra of radical species such as  $CH$ ,  $C_2$ , and  $H$  (Balmer series) can be identified and analyzed using OES.

## Observations:

Chamber pressure (Torr)	Plenum (Torr)	Microwave power (kW)	Temperature ( $^{\circ}C$ )	H2 flow (SCCM)	CH4 flow (SCCM)
$60 \pm 0.1$	$20 \pm 1.5$	$2000 \pm 10$	$475 \pm 1$	$500 \pm 5$	$50 \pm 5$